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Gate Protective Device for SOS Array

The problem:

One of the problems in CMOS (complementarysymmetry metal-oxide semiconductor) technology is that SOS (silicon oxide on sapphire) arrays are subject to breakdown voltages caused by electrostatic discharge from a person or a piece of equipment in contact with the external leads of the circuit. Because breakdown voltage BV_{ox} across thin (1000 angstroms) gate oxides is about 70 volts, it can be easily exceeded by such discharges.

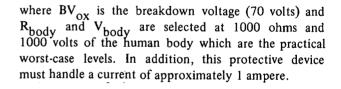
How it's done:

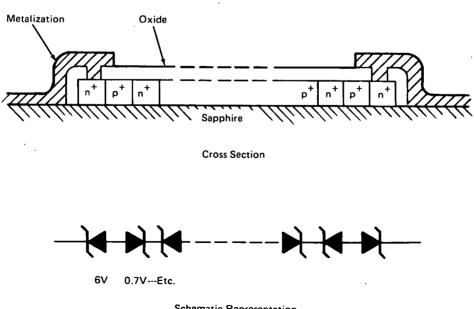
As a function of the human body resistance, the limiting of transient voltage across the gate oxide requires that the dynamic impedance R_{dyn} of the protective device be

$$R_{dyn} \leq \frac{BV_{ox}}{V_{body}} R_{body}$$

The solution:

A gate protective device was made which consists of alternate heavily doped n^+ and p^+ diffusions to eliminate the problem.





Schematic Representation

(continued overleaf)

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A device satisfying these requirements consists of alternate heavily doped n⁺ and p⁺ diffusions which are easily produced during the normal double epitaxial processing. Schematically, this device represents a series of reversebiased zener diodes and alternate forward diodes, as shown in the figure. For a junction doped heavily on both sides $(10^9/\text{cm}^3)$, the zener breakdown voltage is approximately 6 volts. Thus, for a string of 2n junctions, there are n 6-volt zener diodes and n forward diode drops of approximately 0.7 volt each in series. The total voltage drop can be easily fixed with the appropriate number of junctions.

Several devices of this geometry were made which consisted of nine alternately diffused strips (eight junctions). Results showed that each device had a 27-volt breakdown in either direction. This breakdown was reproducible across the entire wafer with a tolerance of better than ± 2 volts.

Note:

Requests for further information may be directed to: Technology Utilization Officer NASA Headquarters Code KT Washington, D. C. 20546 Reference: B72-10755

Patent status:

Title to this invention has been waived under the provisions of the National Aeronautics and Space Act [42 U.S.C. 2457 (f)], to the RCA Corp., Princeton, N. J. 08540.

Source: J. E. Meyer, Jr. and J. H. Scott of David Sarnoff Research Center of RCA Corp. under contract to NASA Headquarters (HQN-10745)

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